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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/540,610	03/31/2000	James E. Nulty	16820.P097	2171
26263 7	7590 05/20/2003			
SONNENSCHEIN NATH & ROSENTHAL P.O. BOX 061080 WACKER DRIVE STATION			EXAMINER	
			CHU, CHRIS C	
CHICAGO, IL 60606-1080			ART UNIT	PAPER NUMBER
			2815	17
			DATE MAIL ED. 05/20/2002	1/

Please find below and/or attached an Office communication concerning this application or proceeding.



		\mathcal{M}_{-}
	Application No.	Applicant(s)
	09/540,610 NULTY ET AL.	
Office Action Summary	Examiner	Art Unit
	Chris C. Chu	2815
The MAILING DATE of this communicati Period for Reply	on appears on the cover sheet w	ith the correspondence address
A SHORTENED STATUTORY PERIOD FOR THE MAILING DATE OF THIS COMMUNICAT - Extensions of time may be available under the provisions of 37 after SIX (8) MONTHS from the mailing date of this communication of the period for reply specified above is less than thirty (30) datured in NO period for reply is specified above, the maximum statutor Failure to reply within the set or extended period for reply will, the Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b). Status	CFR 1,136(a). In no event, however, may a tition. It is a reply within the statutory minimum of this y period will apply and will expire SIX (6) MOI by statute, cause the application to become A	reply be timely filed rly (30) days will be considered timely. NI HS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).
1) Responsive to communication(s) filed	on <u>11 March 2003</u> .	
2a)⊠ This action is FINAL . 2b)[This action is non-final.	
3) Since this application is in condition for closed in accordance with the practice		
Disposition of Claims	and the address	
4)⊠ Claim(s) <u>25 - 39</u> is/are pending in the a	• •	
4a) Of the above claim(s) is/are v	vithdrawn from consideration.	
5) Claim(s) is/are allowed.		
6)⊠ Claim(s) <u>25 - 39</u> is/are rejected.		
7) Claim(s) is/are objected to.		
8) Claim(s) are subject to restriction Application Papers	and/or election requirement.	
9) The specification is objected to by the E	caminer.	
10) The drawing(s) filed on is/are: a)[the Examiner.
Applicant may not request that any objecti		
11) The proposed drawing correction filed or	***	•
If approved, corrected drawings are requir		,,
12) The oath or declaration is objected to by	the Examiner.	
Priority under 35 U.S.C. §§ 119 and 120		
13) Acknowledgment is made of a claim for	foreign priority under 35 U.S.C	. § 119(a)-(d) or (f).
a) All b) Some * c) None of:		
1. Certified copies of the priority do	cuments have been received.	
2. Certified copies of the priority do	cuments have been received in	Application No.
Copies of the certified copies of the application from the Internation See the attached detailed Office action for the action for th	onal Bureau (PCT Rule 17.2(a))	
14) ☐ Acknowledgment is made of a claim for o	·	
a) ☐ The translation of the foreign langu 15)⊠ Acknowledgment is made of a claim for	age provisional application has	been received.
Attachment(s)	, ,	



Application/Control Number: 09/540,610

Art Unit: 2815

Page 2

DETAILED ACTION

Response to Amendment

1. Applicant's amendment filed on March 11, 2003 has been received and entered in the case.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 25 and $27 \sim 39$ are rejected under 35 U.S.C. 103(a) as being unpatentable over Dennison et al. in view of Figura et al.
- Regarding claim 25, Dennison et al. discloses in column 3, line 35 the etch stop material (20) being silicon nitride.

Regarding claim 27, Dennison et al. discloses in Fig. 2 a structure (10), comprising:

- a conductive layer (12 and column 3, lines 29 ~ 33) disposed over a substrate;
- a first insulating layer (18) on the conductive layer;



Application/Control Number: 09/540,610 Art Unit: 2815 Page 3

- a contact region (the area of 34) in the first insulating layer;
- at least one insulating spacer (18) in the contact region adjacent to the first insulating layer (see Fig. 2); and
- an etch stop material (20 and column 3, line 35) over the first insulating layer and adjacent to the insulating spacer (see Fig. 2).

Dennison et al. does not disclose the etch stop material being a different material from the insulating spacer. However, Figura et al. discloses in Fig. 1 an etch stop material (column 4, lines 51 and 52) being a different material from the insulating spacer (column 4, lines 11 and 12). Thus, it would have been obvious to one of ordinary skill in the art at the time when the invention was made to modify Dennison et al. by using different materials for the etch stop material and the insulating spacer as taught by Figura et al. The ordinary artisan would have been motivated to modify Dennison et al. in the manner described above for at least the purpose of minimizing current leakage and short circuits (column 2, lines 36 ~ 38).

Regarding claim 28, Dennison et al. discloses in Fig. 2 the insulating spacer (18) having a substantially rectangular profile in the contact region (see Fig. 2).

Regarding claims 29 and 36, Dennison et al. discloses in Fig. 2 the insulating spacer (18) having a surface portion in the contact region without overlying etch stop material (see Fig. 2).

Regarding claims 30 and 37, Dennison et al. discloses in Fig. 2 the insulating spacer (18) surface portion without overlying etch stop material comprising an insulating spacer surface portion most distant from the substrate (see Fig. 2).

Regarding claim 31, Dennison et al. discloses in Fig. 2 the insulating spacer (18) having a surface portion in the contact region without overlying etch stop material (see Fig. 2).



Application/Control Number: 09/540,610

Page 4

Art Unit: 2815

Regarding claims 32 and 38, Dennison et al. discloses in Fig. 2 a structure (10), further comprising a second insulating layer (28) on the etch stop layer and over the conductive layer (see Fig. 2).

Regarding claims 33 and 39, Dennison et al. discloses in Fig. 2A a structure (10), further comprising a second conductive material (40) in the contact region (see Fig. 2A).

Regarding claim 34, Dennison et al. discloses in Fig. 2 a structure, comprising the step of:

- a first electrically conductive material (24) formed in and/or on a surface of a substrate;
- a contact opening (the area of 34) in a region adjacent to a second electrically conductive material (the area of 40 in Fig. 2A) formed on the substrate;
- an electrically insulative spacer (18) in the contact opening adjacent to the second electrically conductive material (see Fig. 2);
- an etch stop material (20) over the electrically insulative spacer and the first and second electrically conductive materials (see Fig. 2);
- a blanket layer (28) over the etch stop material; and
- an opening through a first part of the etch stop material to the first electrically conductive material (see Fig. 2).

Dennison et al. does not disclose the etch stop material being a different material from the insulating spacer. However, Figura et al. discloses in Fig. 1 an etch stop material (column 4, lines 51 and 52) being a different material from the insulating spacer (column 4, lines 11 and 12).

Thus, it would have been obvious to one of ordinary skill in the art at the time when the



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